



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Toshihiro YAMASHITA, et al.

Serial No.: 09/901,038 Group Art Unit: 1765

Filed: July 10, 2001 Examiner: D.V.D. Nguyen

PLASMA PROCESSING SYSTEM IN WHICH WAFER IS RETAINED BY For:

GROUP TOO ELECTROSTACTIC CHUCK, PLASMA PROCESSING METHOD AND METHOD OF

MANUFACTURING SEMICONDUCTOR DEVICE

RESPONSE TO RESTRICTION REQUIREMENT

Commissioner for Patents Washington, DC 20231

Sir:

Noting the Office Action of March 25, 2003 wherein restriction has been required, Applicant(s) hereby elect Group I (claims 1-8) for prosecution in the above-identified application.

To the extent necessary, a petition for an extension of time under 37 C.F.R. 1.136 is hereby made. Please charge any shortage in fees due in connection with the filing of this paper, including extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

Respectfully submitted,

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Date: April 21, 2003